

METHOD AND APPARATUS FOR INSPECTING RESIST PATTERN

ABSTRACT OF THE DISCLOSURE

A method and apparatus for inspecting a resist pattern formed on an anti-reflection coating to detect defects by applying light to the resist pattern and visually observing light diffracted from the resist pattern. Light is applied to the resist pattern from a light source at an incident angle of 45 degrees or less with respect to the top surface of the resist pattern. An inspector positioned on the same side as the light source determines the presence or absence of a defective portion of the resist pattern by visually observing light diffracted to the same side as the light source. The defective portion of the resist can be visually distinguished from the non-defective portion by the brightness and color of the light diffracted to the same side as the light source.